ABSTRACT

Device for Etching or Precipitation Using a Plasma

In order to provide for a simple, reasonable, especially long-lived plasma etching device on the basis of a known device for etching or precipitation using a plasma, with a reaction chamber for the uptake of a substrate to be treated comprising a gas inlet nozzle of quartz glass for feeding a gas into the reaction chamber, and a plasma generator for the generation of plasma within the inlet nozzle, the proposal according to the invention is to arrange a shielding element between the inner walls of the inlet nozzle and the plasma to be generated. A suitable tube-like shielding element for application in such a plasma etching device consists of synthetic quartz glass the inside surface of which is smoothed in a hot process.

Figure 2